
Investor & Analyst Day

July 2021





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Forward Looking Statements

This presentation contains forward-looking statements within the meaning of safe harbor provisions of the Private Securities Litigation Reform Act of 1995 relating to future events or our future performance, such as statements regarding, but are not limited to, anticipated growth opportunities and projections about our business and its future revenues, expenses and profitability. Forward-looking statements involve known and unknown risks, uncertainties and other factors that may cause our actual results, levels of activity, performance or achievements to be materially different from any future results, levels of activity, performance or achievements expressed or implied in those forward-looking statements. Factors that may affect our results, performance, circumstances or achievements include, but are not limited to, the following: catastrophic events such as the outbreak of COVID-19; increased information technology security threats and sophisticated computer crime; foreign political and economic risks; changes in U.S. trade policies; inability to protect intellectual property; open source technology exposure; failure to compete effectively or to respond to the rapid technological changes; consolidation in our industry; difficulty to predict the length and strength of any downturn or expansion period of the market we target; factors that adversely affect the pricing and demand for our product lines; dependency on a small number of large customers; dependency on a single manufacturing facility per product line; dependency on a limited number of suppliers; lengthy sales cycle and customer delays in orders; political, economic, and military instability in Israel; risks related to our convertible notes; currency fluctuations; and quarterly fluctuations in our operating results. We cannot guarantee future results, levels of activity, performance or achievements. The matters discussed in this presentation also involve risks and uncertainties summarized under the heading "Risk Factors" in Nova's Annual Report on Form 20-F for the year ended December 31, 2020 filed with the Securities and Exchange Commission on March 1, 2021.

These factors are updated from time to time through the filing of reports and registration statements with the Securities and Exchange Commission. Nova Measuring Instruments Ltd. does not assume any obligation to update the forward-looking information contained in this presentation. This presentation includes financial measures that exclude charges for amortization of acquired intangible assets, net adjustment of deferred tax assets, stock-based compensation expenses and expense related to royalty buyout agreement with the Office of the Chief Scientist and inventory write-off and are therefore not calculated in accordance with generally accepted accounting principles (GAAP). Management believes that these non-GAAP financial measures provide meaningful supplemental information regarding Nova's performance because they reflect our operational results and enhances management's and investors' ability to evaluate Nova's performance before charges or benefits considered by management to be outside Nova's ongoing operating results. The presentation of this non-GAAP financial information is not intended to be considered in isolation or as a substitute for the financial information prepared and presented in accordance with GAAP. Management believes that it is in the best interest of its investors to provide financial information that will facilitate comparison of both historical and future results and allows greater transparency to supplemental information used by management in its financial and operational decision making. A reconciliation of each GAAP to non-GAAP financial measure discussed in this presentation is contained in the accompanying financial tables.

Today's Agenda



Eitan Oppenheim

President & CEO

Performance highlights
and strategic plans



Dror David

CFO

Financial milestones
and future directions



Zohar Gil

CMO & BD

Industry forecast
and Nova's growth
engines



Dr. Shay Wolfling

CTO

It's all about technology
and differentiation



Closing remarks

Q&A



Performance Highlights and Strategic Plans

Eitan Oppenheim, President & CEO



Nova is a leading innovator and a key provider of **metrology** solutions for advanced **process control** used in semiconductor manufacturing



Key Facts

Post COVID

1993

Date Founded
Dually Traded

Major Sites

USA & Israel

\$325M (TTM)

Revenues- Accelerated
organic growth

\$480M

Gross cash reserves

25%

R&D investment in
new technologies

800

HQ & global employees -
hiring rally

2.8B (TTM)

Market Cap-
significant growth

Resiliency

50% production output growth

3

New technologies
launched

440

Patents - accelerated IP
Protection

Unique Portfolio
Dimensional and Materials



Disruptive Technology
X-Ray and Optical, HW and SW



Diversified Exposure
Segments, Customers, Territories



Solid Operational Model
Agility, Efficiency, Profitability



Cultural Advantage
Leadership, Values, Social Responsibility



**Strong
Fundamentals**

Memory Transistor



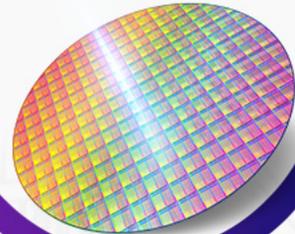
30 Pairs



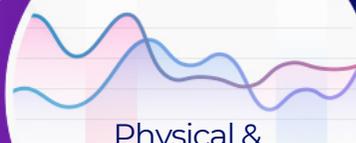
150 Pairs



Optical/X-Ray

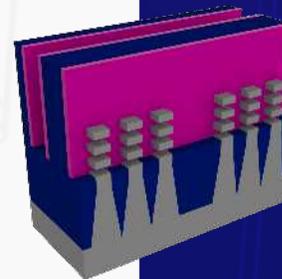


Physical & Mathematical Algorithms



Measuring The Invisible

Logic Transistor



150M Transistors



2015

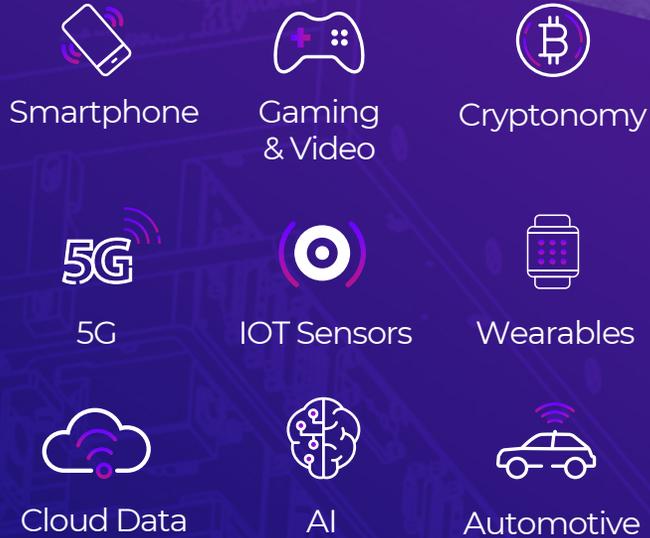
11.8B Transistors



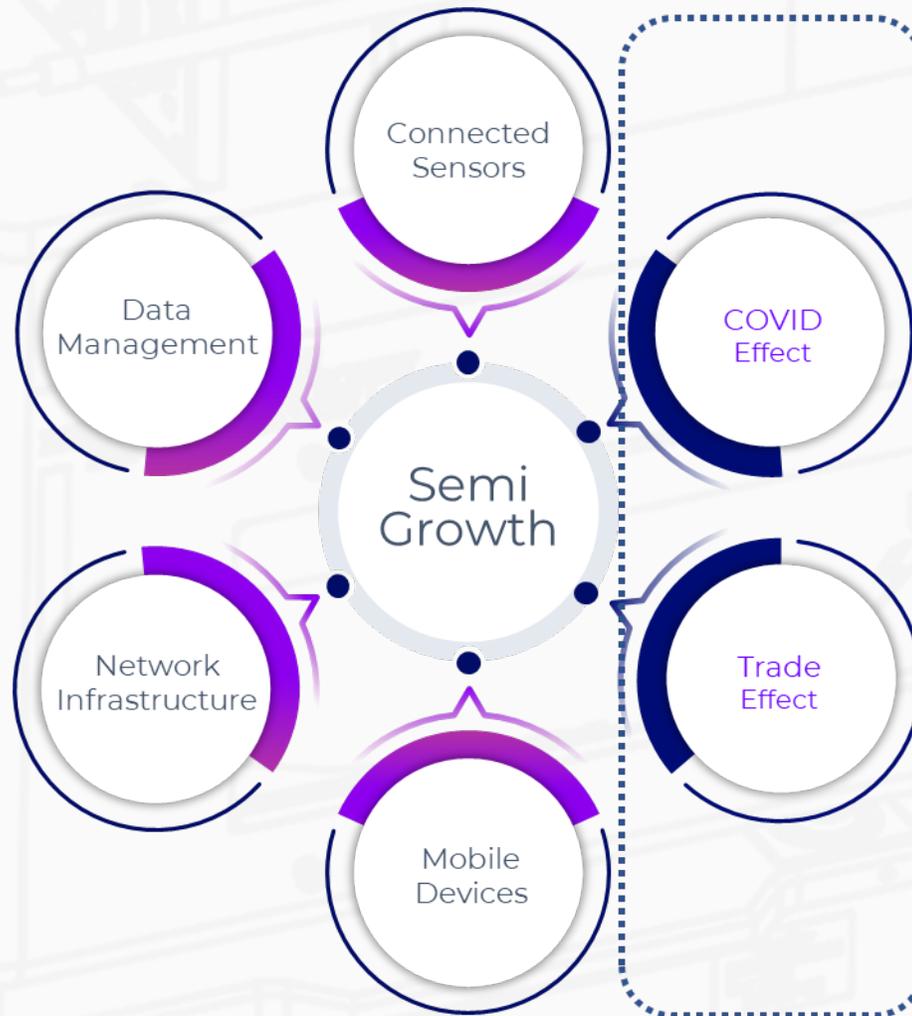
2020

Growing Demand

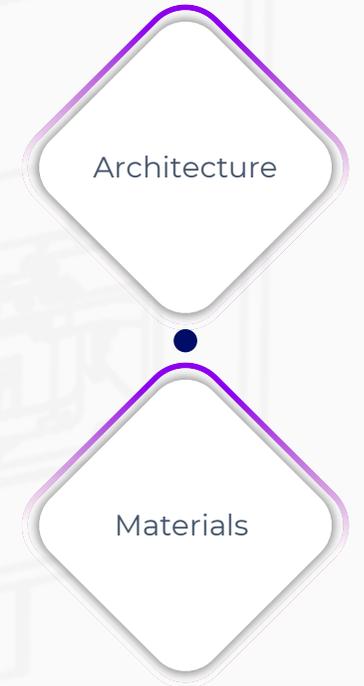
Semiconductors enable advanced digitization



1 Capacity Growth



2 Beyond Capacity Performance Demand



Acceleration

Explosion

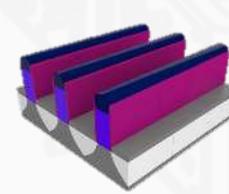
Enablement

Dimensional Metrology Intensity

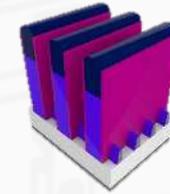
- Scaled devices
- 3D profiles
- Multiple parameters
- Thinner films
- Packaging

Increasing Complexity = Growing Demand

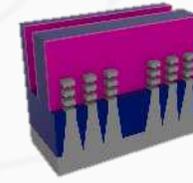
Intensity ↑



Planar



FinFet



Nano Sheet

Logic



Single Stack



Multi-deck



Over Periphery

3D NAND



1Y



1a



1b

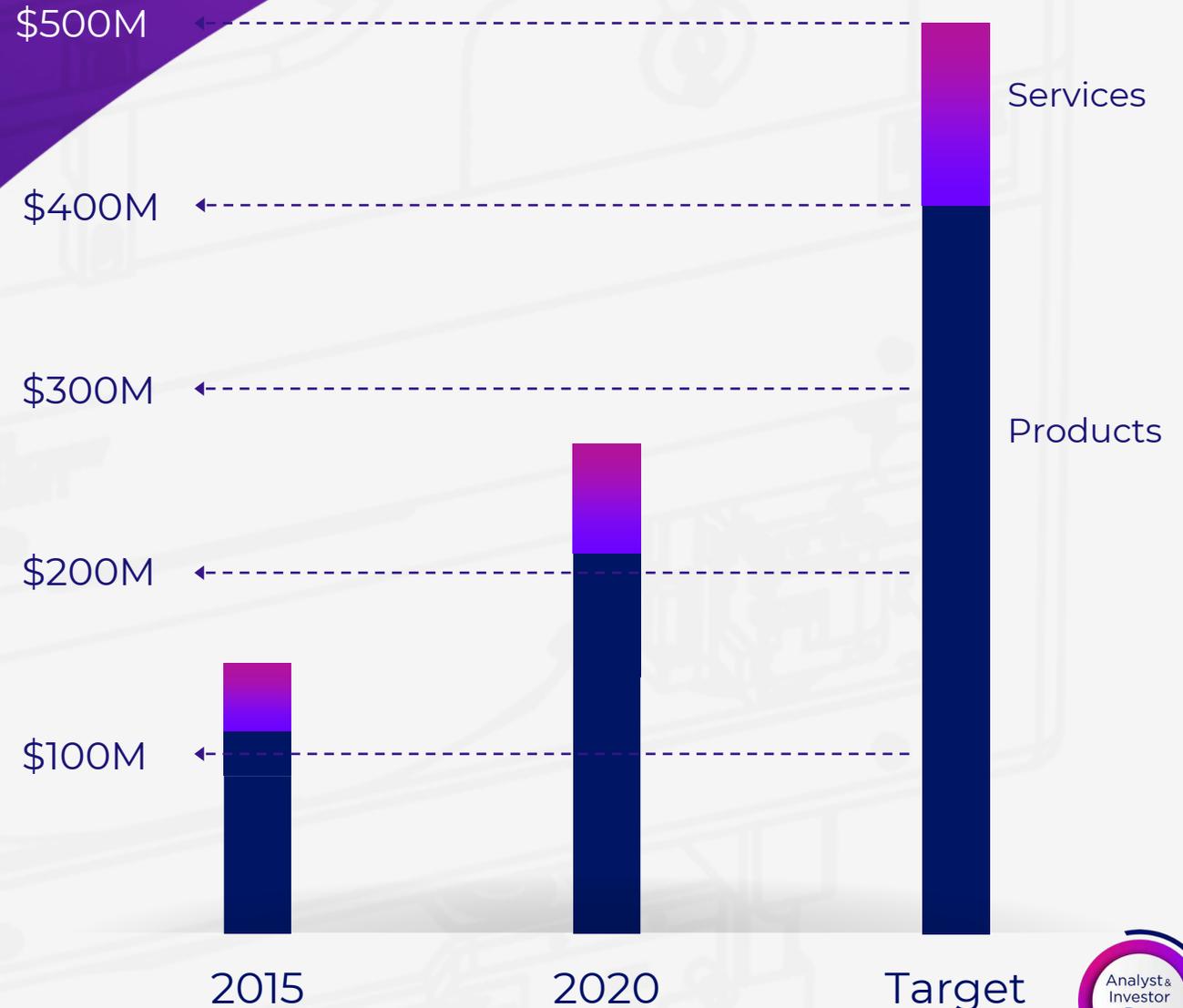
DRAM

Scale & Complexity →

Nova 500

Organic Growth

- Share gains
- TAM expansion
- Disruptive innovation
- SW HW optimization
- Installed base utilization



Source: company financial information
Non-GAAP financials

Organic Growth Engines



Differentiated technology

Innovative metrology



Physical and ML algorithms

Deep tech data-driven solutions



Service revenue

Extendibility & enhancement



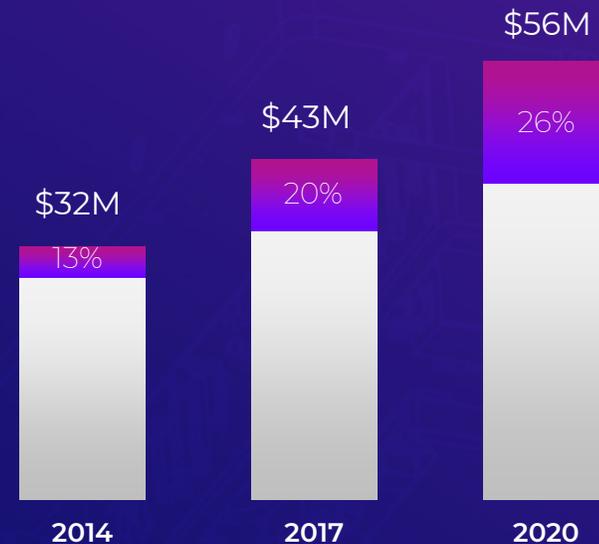
Research technologies

LAB to FAB

Total Organic Addressable Market



Investment in New Technologies (of Total R&D, Gross)



Inorganic Approach

Search Guidelines

-  **Early access**
Lab to Fab technology
-  **Materials Leadership**
-  **Software offering**
Enhancement
-  **Adjacent**
Process control markets

Screening Elements

Top line synergy

Complementary technology

Operational leverage (accretion)

Diversification within core capabilities



Financial Milestones & Future Directions

Dror David, CFO

Dror David

Chief Financial Officer



- Joined Nova in 1998.

- Appointed as CFO in 2005.

- Beforehand, held positions of Company Controller, Vice President of Operations and Vice President of Resources in charge of finance, operations, IT and HR.

- Led Nova's private placement in 2007, secondary public offering in 2010 and bond issuance in 2020.

H1 2021* Financial Performance

* Including Q2 2021 Mid-Guidance

Sustainable Profitable Annual Growth

2020 Performance

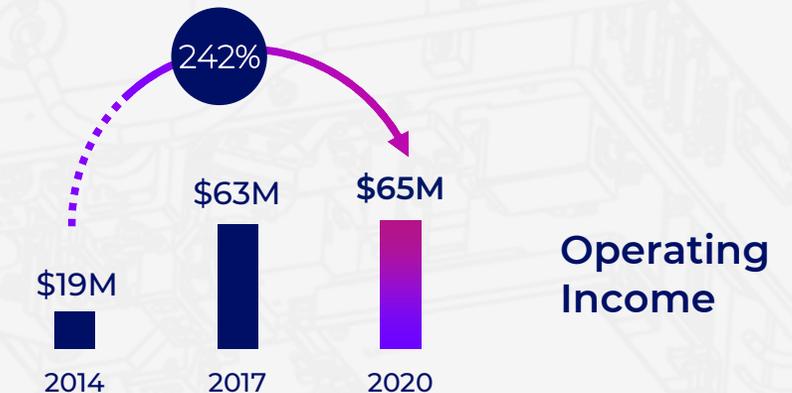
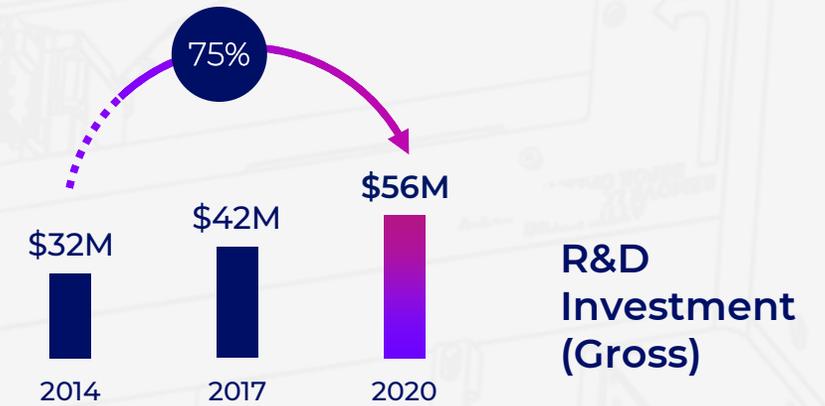
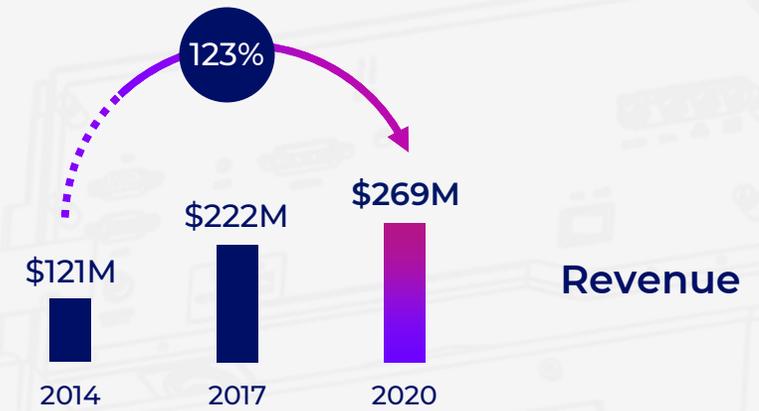
13%
Revenue CAGR

24%
Operating income CAGR

\$269M
Revenue

24%
Operating margin

CAGR – 2015-2020
Non-GAAP Financials



NOVA



Financial Performance Half Year

Continuous Revenue Growth



Earnings Per Share (Non-GAAP)



Note: Our non-GAAP measures are not meant to be considered in isolation or as a substitute for comparable GAAP measures and should be read only in conjunction with our consolidated financial statements prepared in accordance with GAAP, available on our website.

Segments



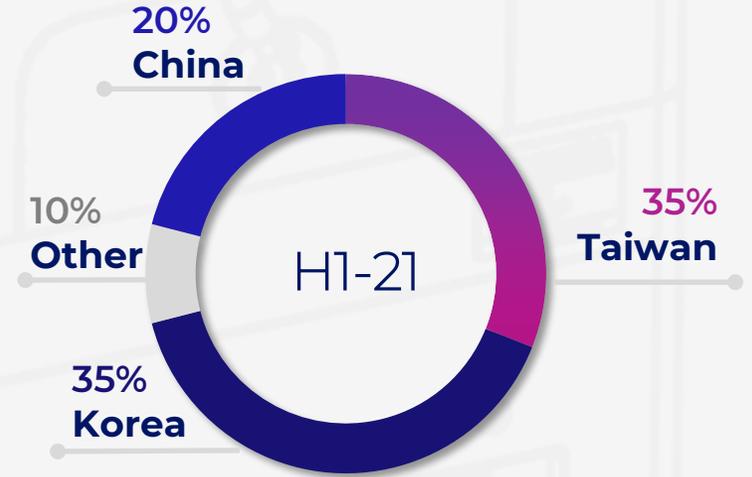
Logic/Foundry strength

Nodes



Multiple end market dynamics

Geography Revenues



3 large territories
US gaining momentum

Nova 500 Financial Model

Business Tailwind



Overall TAM Growth



Market Share Gains



Software Revenues



High Value of New Technologies

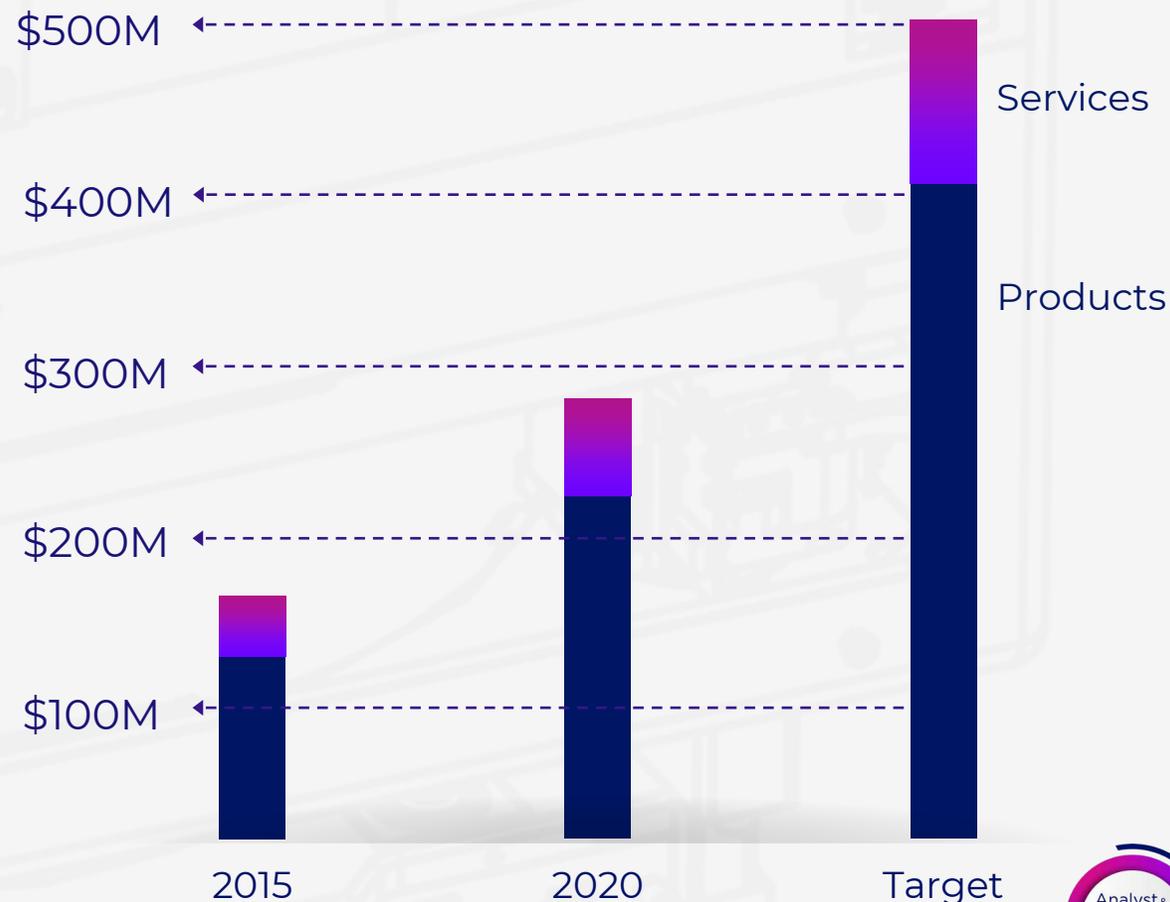


Leverage Installed-Base

Target Revenue

Organic Growth

- Share gains
- TAM expansion
- Disruptive innovation
- Market tailwinds
- Installed base utilization



Source: company financial information
Non-GAAP Financials

Infrastructure Projects



Industry 4.0 and
New Cleanroom

\$12M
(2022)



Global IT Networks
and Applications

\$5M
(2022-2023)



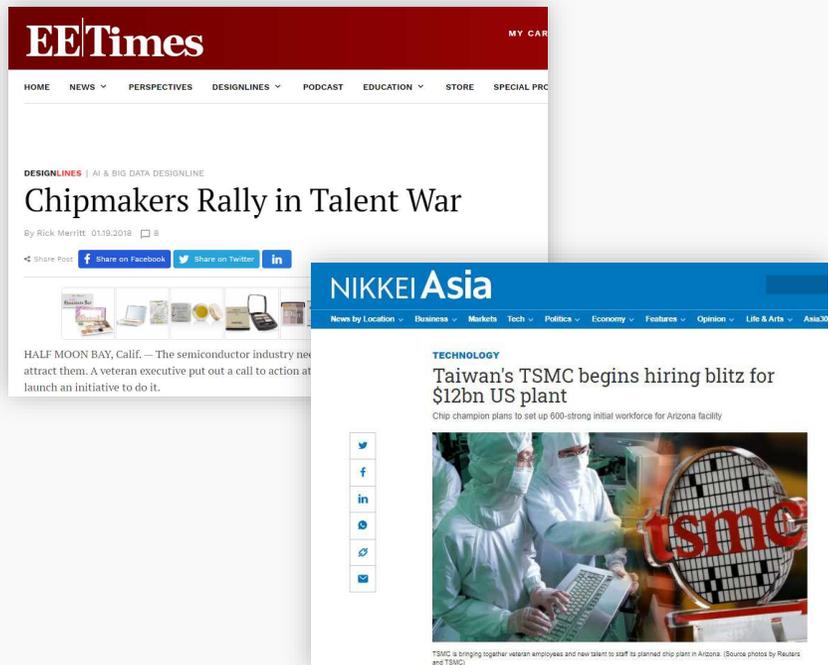
Locations-
US, China, Ireland

\$2M
(2021-2022)

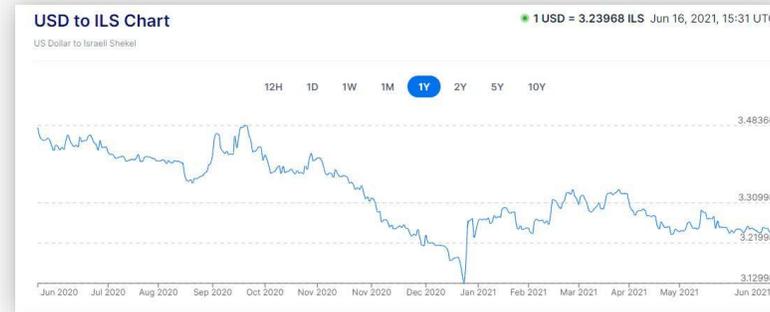
Cost Trends

Talent Costs

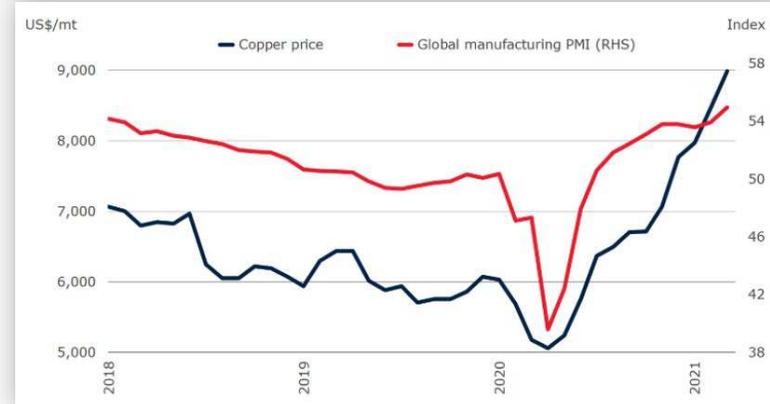
Increased demand for talent across territories:
US | Israel | Taiwan



Macroeconomics



Exchange rates

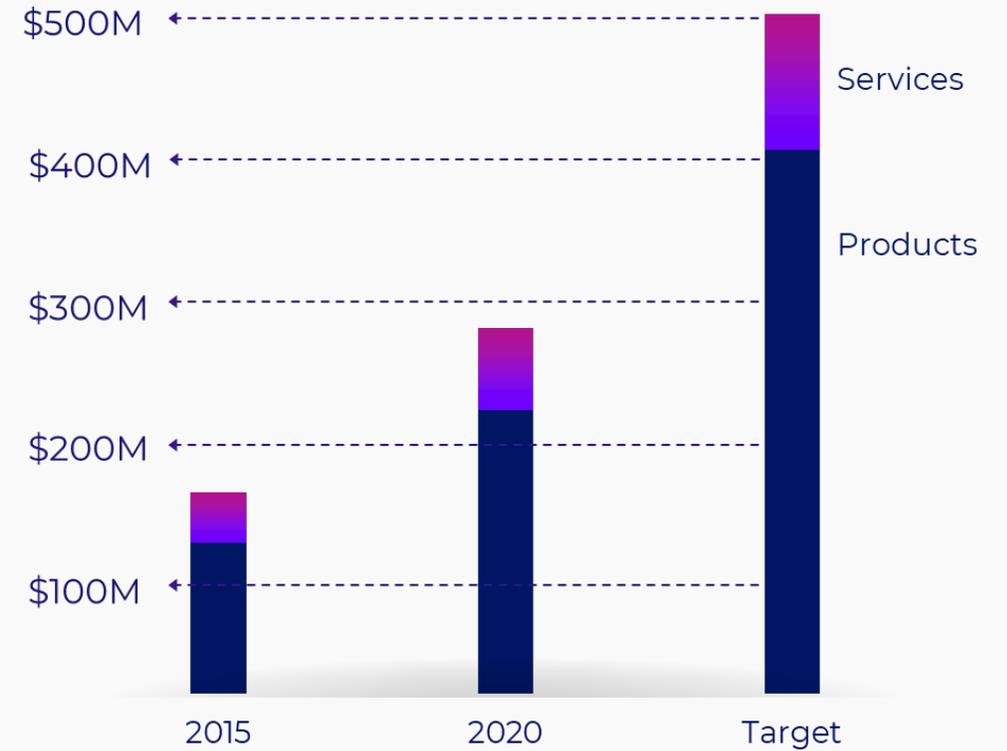


Copper prices and global manufacturing PMI

Source: World Bank, March 2021, xe.com, June 2021

Financial Target Model

Revenue	R&D Investment	Tax
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\$500M	17%-19%	15% (IL-13%, US-18%)
Gross Margin	SG&A	Share Count
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57-59%	13%-15%	32M



Operating Margin

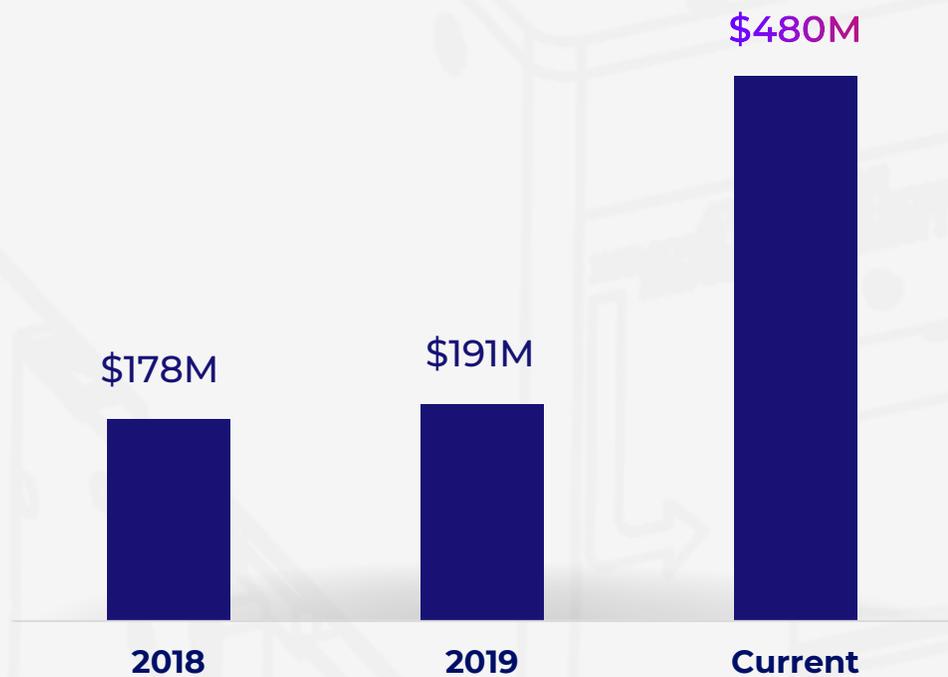
26-29%

Quarterly Earnings

Power of \$1 EPS

Capital Allocation Plans

Gross Cash Reserves



Enabling inorganic growth

Facilitating continuous investment

\$200M convertible debt due 2025

Capital Allocation Plans



IT & New Sites:
\$10M



Manufacturing Facilities:
\$12M



Working Capital:
\$40M-\$50M



Baseline 20% Revenue:
\$80M-\$100M



M&A
Opportunities:
\$300M-\$350M



Shareholders
Return

Inorganic Approach

Search Guidelines



Early access
Lab to Fab technology



Materials Leadership



Software offering
Enhancement



Adjacent
Process control markets

Screening Elements

Top line synergy

Complementary technology

Operational leverage (accretion)

Diversification within core capabilities

Revera Case Study

X-Ray revenue growth

X-Ray & Optical synergy

Accretion day 1
50% EPS growth Y2

Within process control

Non-GAAP Financials

NOVA





Industry Forecast and Nova's Growth Engines

Zohar Gil, CMO & BD

Zohar Gil

Chief Marketing and Business Development Officer



- Joined Nova in 2011.
- Appointed as CMO in 2016.
- Beforehand, held senior positions of marketing and business development at Nova and in Israeli high-tech companies.
- Engineering and Executive MBA from Tel Aviv and Northwestern Universities.

The Revolution of Digitization and Deep Tech Innovation



Semiconductors are the Foundation for this Revolution

Semiconductor Demand Driven By Multiple Catalysts



Robotic Process Automation

25%
CAGR



VR

36%
CAGR



Cloud Computing

25%
CAGR



Industrial IoT

23%
CAGR



Autonomous Vehicle

20 TB
Per Car Daily



5G

37%
CAGR



AI

42%
CAGR



2010
Mobile Internet
Mobility



2015
Data Augmentation
Productivity



2020
Enhanced Connectivity
Resiliency



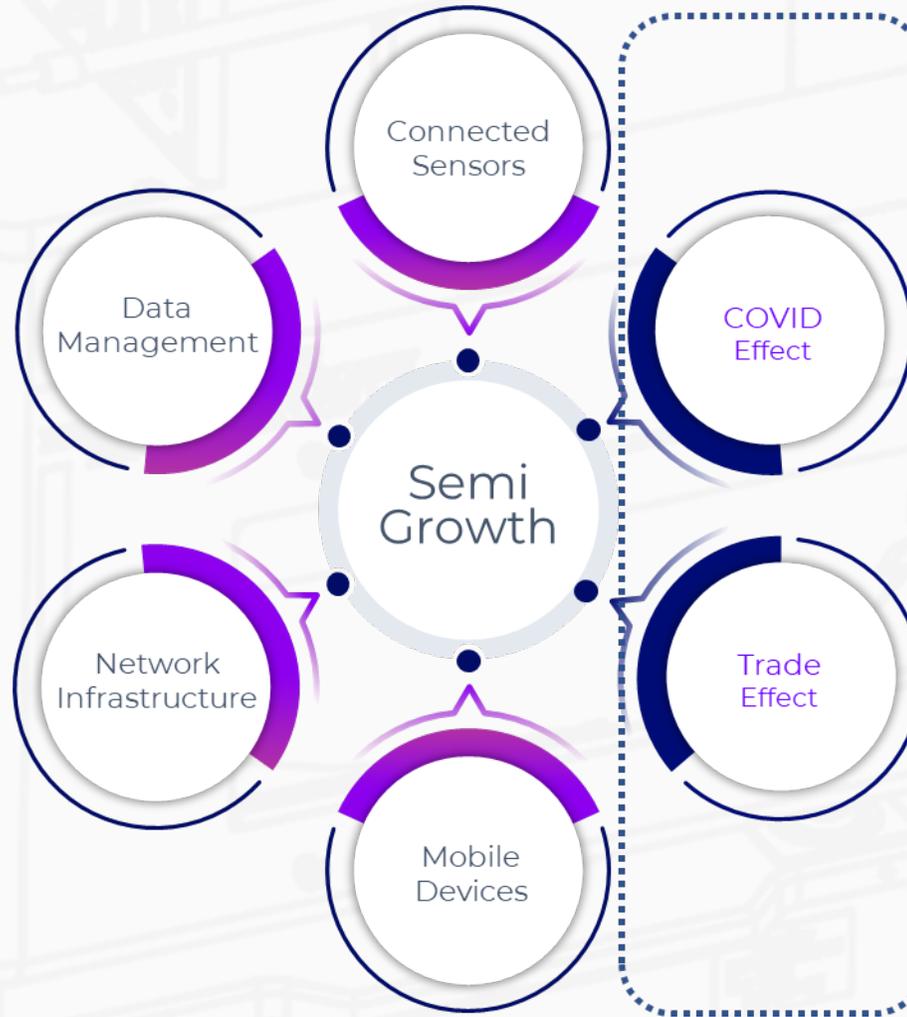
2025
Data Efficiency
Veracity

Growing Demand

Semiconductors enable advanced digitization

- Smartphone
- Gaming & Video
- Cryptonomy
- 5G
- IOT Sensors
- Wearables
- Cloud Data
- AI
- Automotive

1 Capacity Growth



2 Beyond Capacity Performance Demand



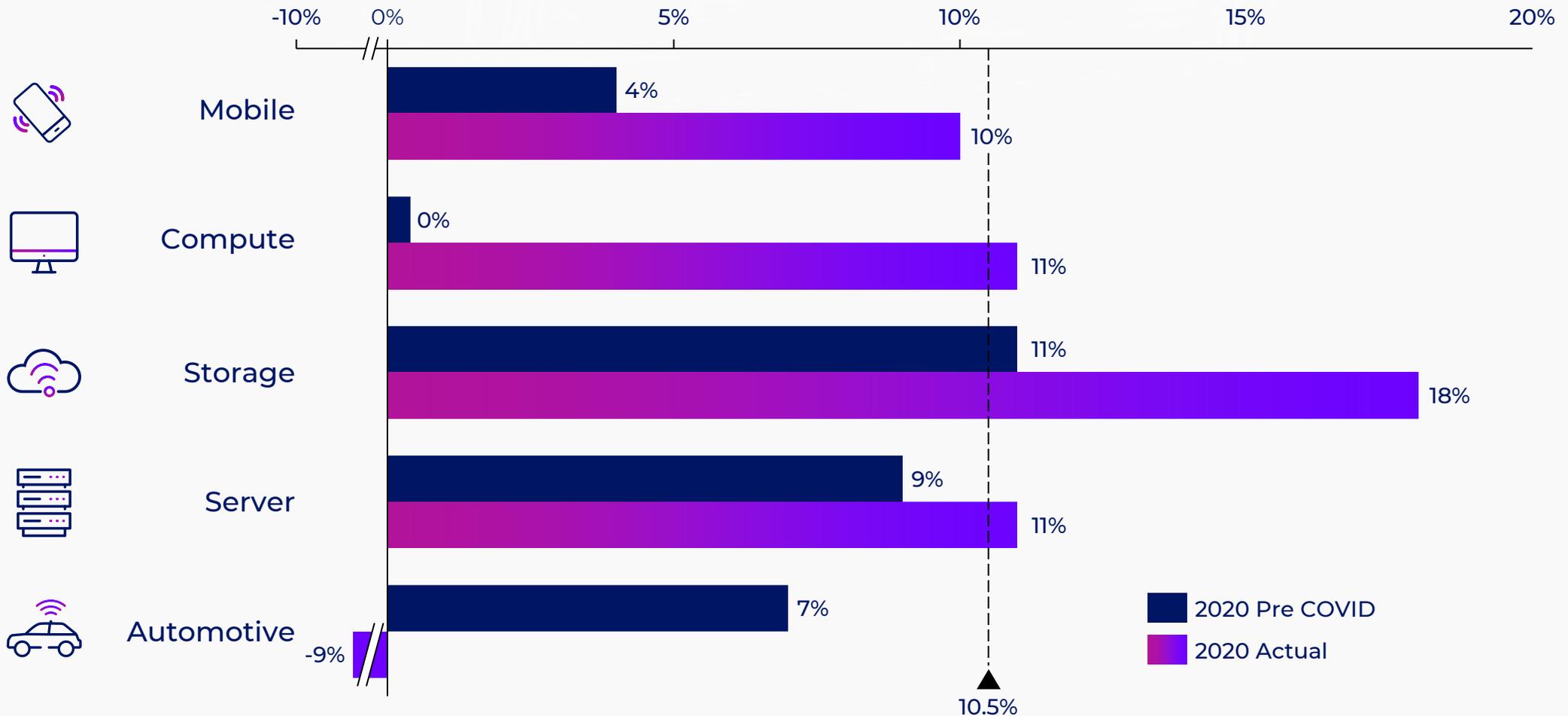
Acceleration

Explosion

Enablement

Semiconductor 2020 – COVID Impact

Semiconductor Segments in 2020 – Pre Covid Prediction vs Actual Growth, %



Source – McKinsey Analysis, May 2021, Gartner Q1/2021

Increase in National Investment in Semi

Government Incentives



CHIPs for America Act



Made in China 2025



2030 Digital Compass



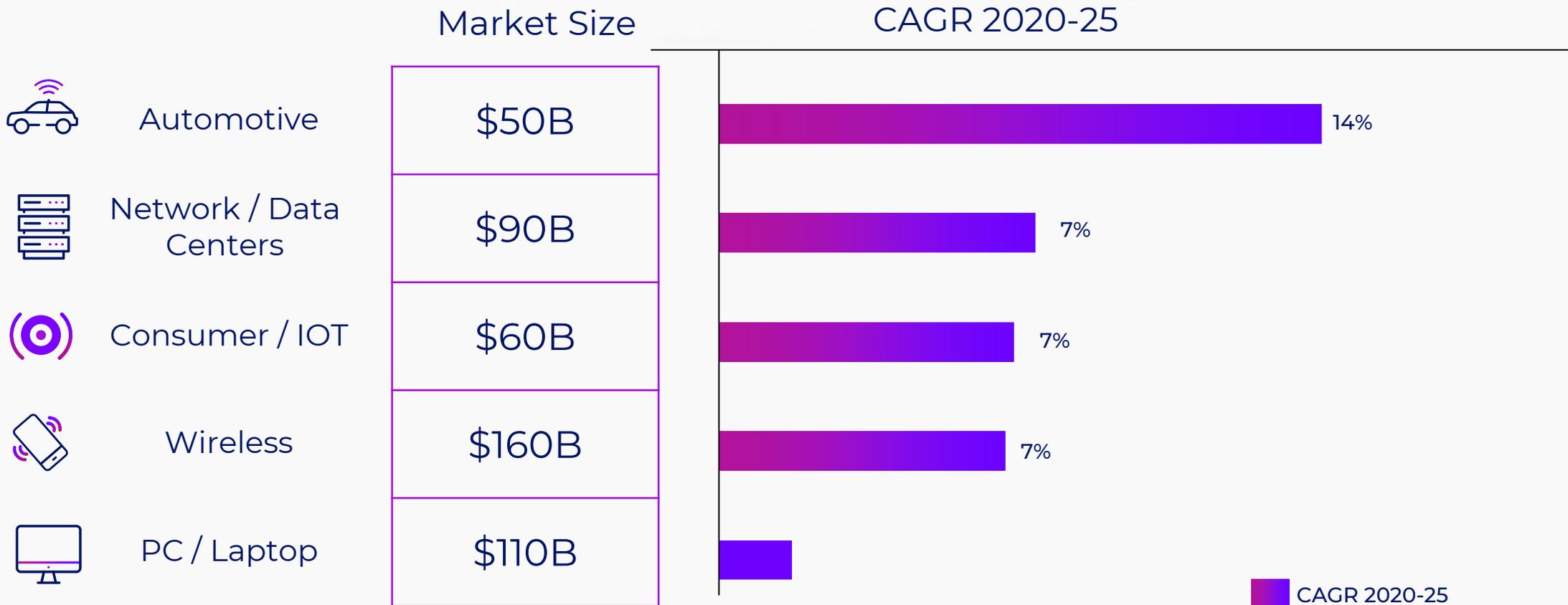
InvesTaiwan



System chips vision and strategy

Key Semi Applications

Growth & Size



IOT Sensor

CAGR 2020-25

Silicon Content Increase

Mobile



Data Storage



Video Game Consoles



Driver Assistance



Trend

4G to 5G

Data Explosion

Cloud & Next Gen

L1/2 to L4/5

Content

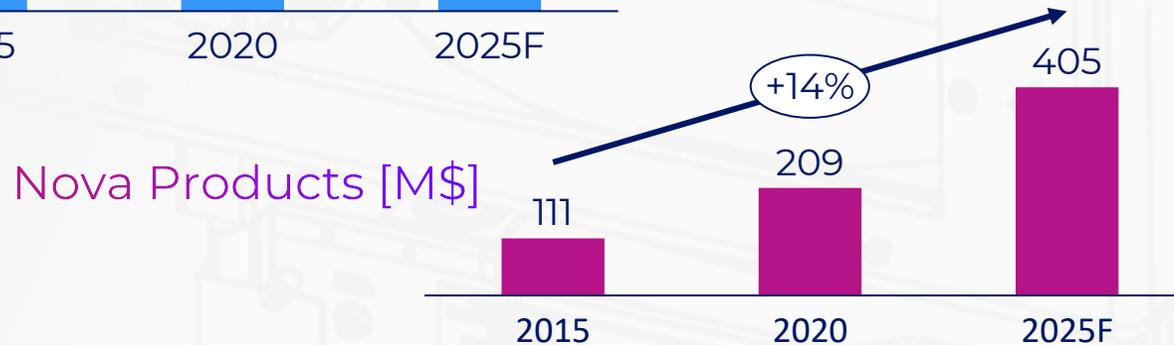
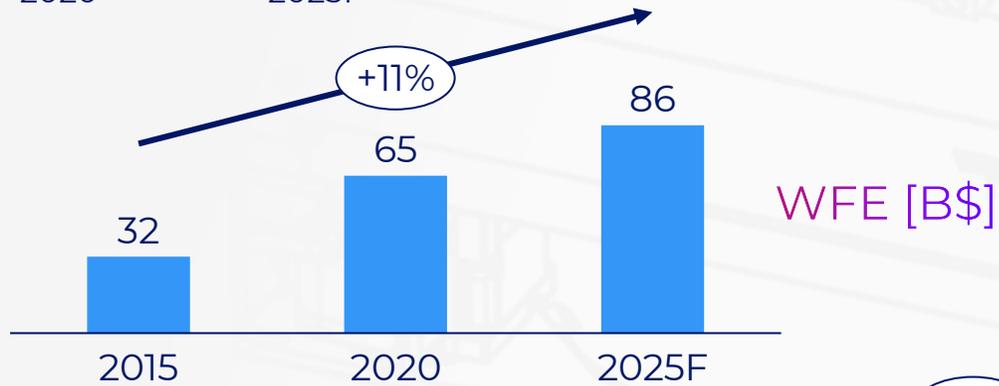
+30%

+30%

+150%

+200%

CAPEX and WFE Outlook



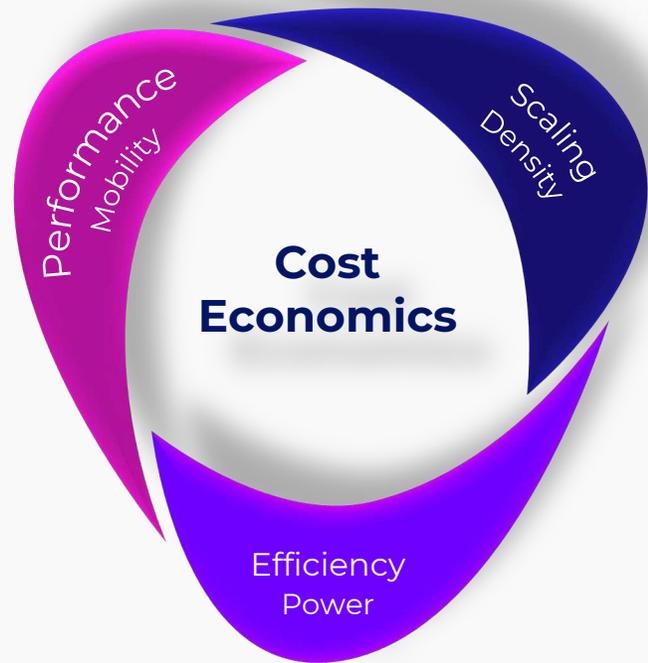
• Semi CAPEX reaching **\$160B** in 2025

• Investment in **all** device segments

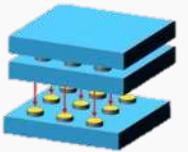
• Nova **outperforming** the market

Semi Technology Inflections

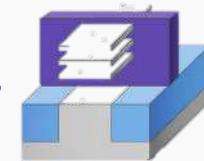
Architectures and Materials



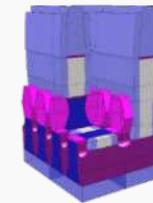
Packaging Schemes



Device Architecture



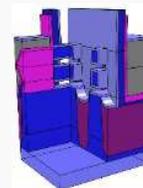
Materials Engineering



3D Memory Structures



Device Scaling



Device Technology Roadmap

Trends and Challenges

2021

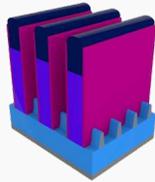
2022

2023

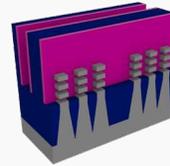
2024

2025

Logic



Transition to
Nanosheet devices



Challenges

- Increased complexity
- More CDs
- Individual properties measurement
- New materials, new metals in BEOL

NAND



3D scaling to
multi/triple deck
3D-NAND



- CMOS under array/wafer bonding
- Multi/triple-deck - high aspect ratio
- Structural and Material challenges

DRAM



Continued scaling to
1c/1d DRAM



- Scaling, process margin (overlay and CD)
- Wafer edge yield, storage capacitor
- CDs, films, profiles, residues, defectivity

Dimensional Metrology

Integrated Metrology

NOVA i570



NOVA ASTERA



- Extending Nova IM Leadership
- Targeting high volume production and R&D of next generation nodes
- Adopted by all leading customers

Stand Alone Metrology

NOVA PRISM



- A New Dimension in Optical CD
- Addressing advanced metrology challenges in logic, 3D-NAND and DRAM
- Adopted by leading logic and memory customers

Over \$700M Addressable Market

Materials Metrology

X-Ray Metrology

NOVA VERAFLEX IV



- Adopted by all the leading customers
- Marking Nova's materials metrology leadership

Optical Metrology

NOVA ELIPSON



- In-line Raman Spectroscopy
- Adopted by leading logic and memory customers

Over \$500M Addressable Market

Modeling & Fleet SW Solutions

Physical and Mathematical Modeling

NOVA MARS



NOVA FIT



- Holistic Approach to Modeling Driven Insights
- Unique algorithms solutions and Machine learning leadership

Fleet SW Solutions

Fleet Management



- Central management
- Performance monitoring
- Big data analytics

Adopted by all leading customers



It's all About Technology and Differentiation

Dr. Shay Wolfling, CTO

Dr. Shay Wolfling

Chief Technology Officer



- Joined Nova as CTO in 2011.

- R&D manager at KLA-Tencor-Belgium, leading multidisciplinary metrology & inspection projects.

- Founder and VP R&D of Nano-Or-Technologies, a start-up company with a proprietary 3D optical technology, acquired in 2005.

- PhD in physics from the Hebrew University.

Outline

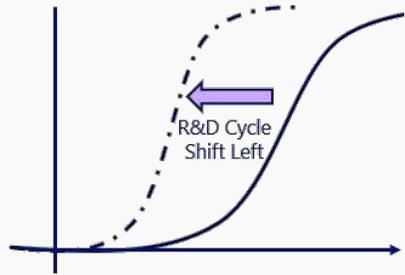
Key Challenges

Unique Technology Solutions

Future Plans

Expanding Challenges at the Advanced Nodes

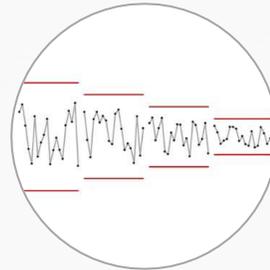
Process Challenges ⇨ Metrology Opportunity



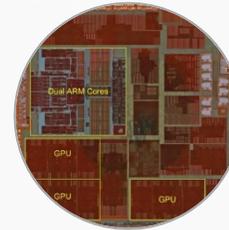
Shorter R&D cycles



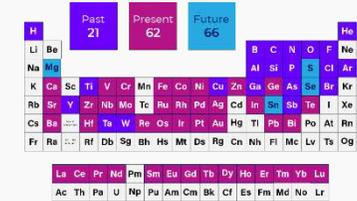
More steps & higher sampling



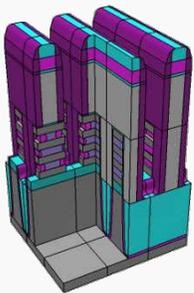
Tighter specs as design rule shrinks



In-die & complex structures



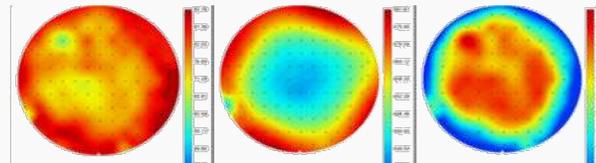
New materials



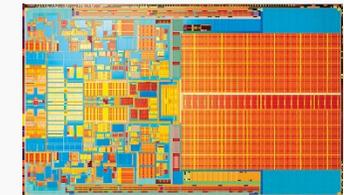
Dimensional complexity increases: 3D devices



High aspect ratio structures



Local variation is critical: local density, Z Profiling



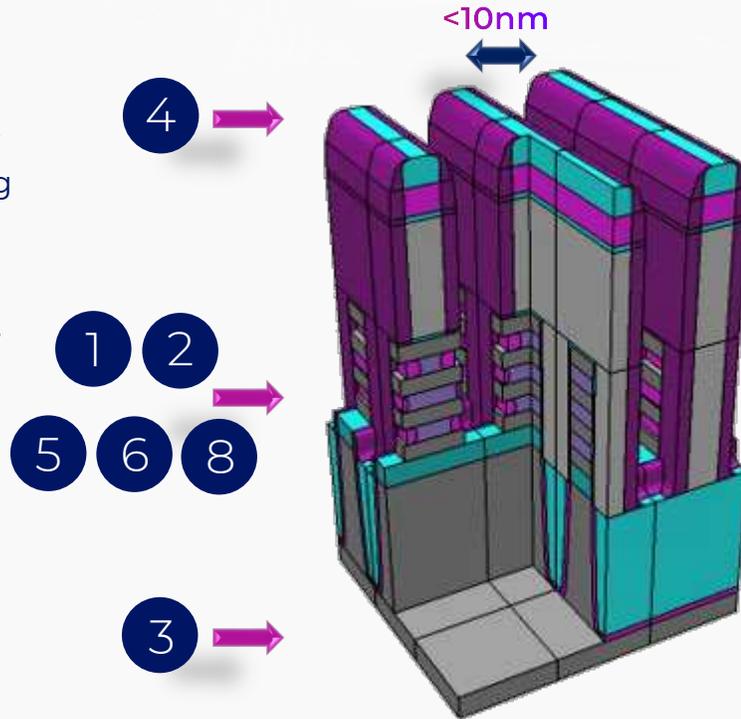
Monitoring more parameters → broader metrology scope

Key Challenges

Across all device segments

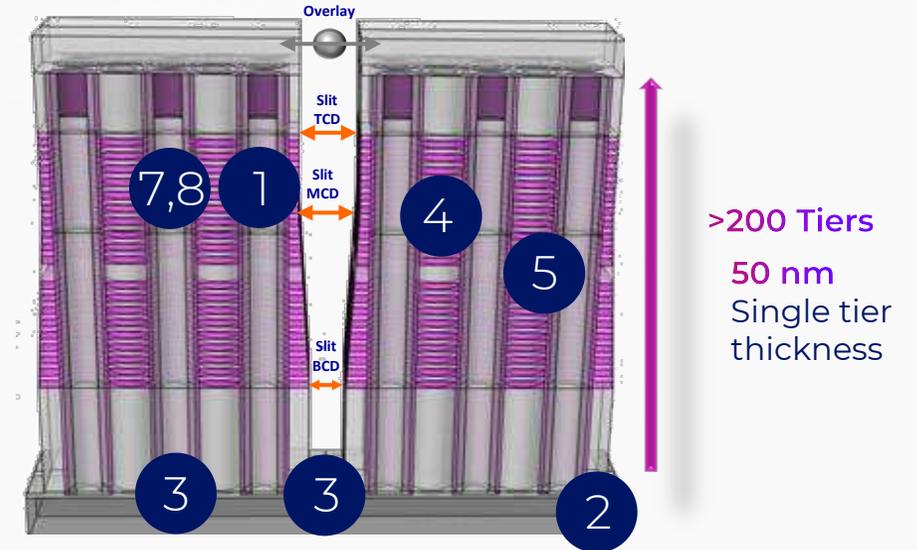
Dimensional

1. Multiple Nanowires – shapes, spacing & thickness
2. Thin deposition surrounding nanosheets
3. Buried structures
4. Local topography variations



Material

5. Si / SiGe uniformity
6. SiGe residues
7. Doping control
8. Stress & strain on multiple nanosheets



Dimensional:

1. HAR channel-hole full profile
2. Underlying logic cell (CuA)
3. Bottom parameters
4. Tiers and liner thickness
5. Multi-deck alignment

Material:

5. Dielectric composition & thickness control
6. Channel Poly Si crystallinity & grain size
7. Channel sidewall
8. Chemical residues

Core Technology

Disruptive Technology

Spectral Reflectometry (SR)

Spectral Interferometry (SI)

X-Ray Photoelectron Spectroscopy (XPS)

Multi Channel Integrated Metrology

X-Ray Fluorescence (XRF)

Advanced X-Ray

Physical Modeling

Raman Spectroscopy

Fleet Management

Mathematical Modeling & Big Data

**Innovative
Approach
to Address
Future Needs**

Unique Technology Solutions

Dimensional

- Critical Dimensions



NOVA ASTERA

Multi-Channel Integrated Metrology
Stand Alone performance in IM

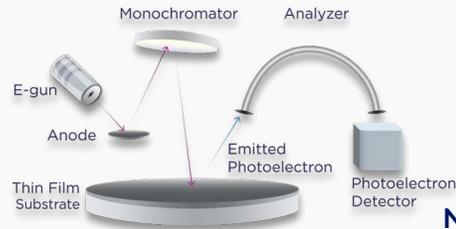


NOVA PRISM

Spectral Interferometry
OCD Full Wavefront Metrology

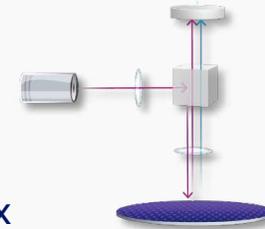
Materials

- Material Properties



NOVA VERA FLEX

X-Ray: XPS and XRF
In-Line composition & thickness



NOVA ELIPSON

Optical: Raman Spectroscopy
In-Line stress / strain and crystallinity

Software & Algo

- Physical & Machine Learning Models
- Big Data Analytics

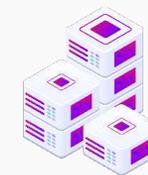


Nova MARS



Nova FIT

Physical & Mathematical Modeling
Combining all types of modeling



Fleet Management

Cloud Based Fleet Management
Smart connectivity

Multi-Channel Integrated Metrology

World-Leading IM Performance

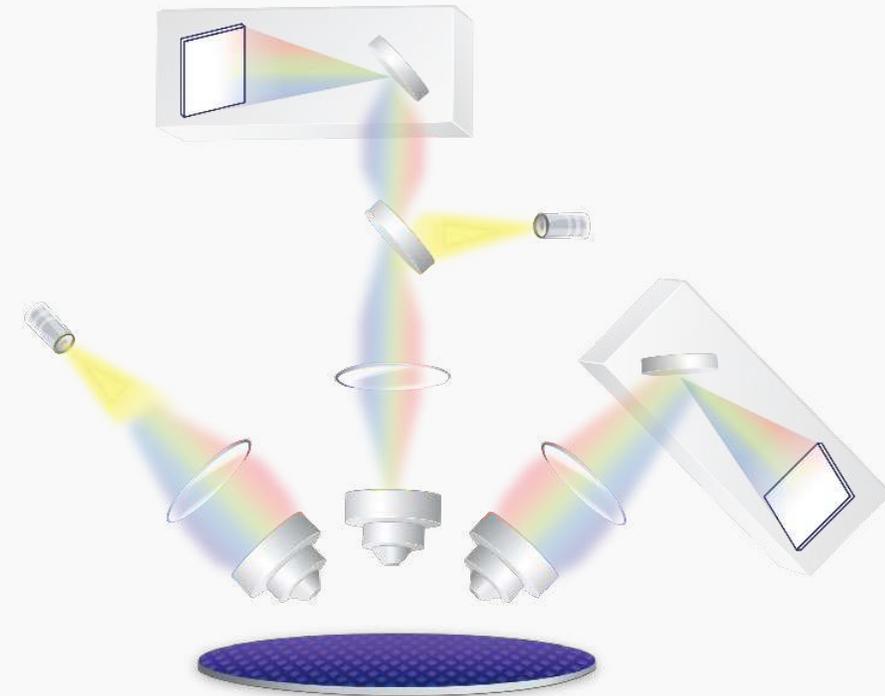


Stand-alone performance in Integrated Metrology form factor

- **World's first** IM with both oblique and normal incidence spectral information
- **Stand-alone level performance:** accuracy, sensitivity, parameters de-correlation
- **Algo:** dedicated modeling and ML package

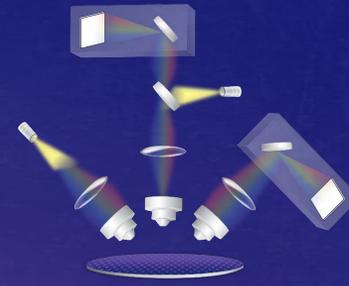
Multiple use-cases

- R&D and pilot
- Complex CMP & etch layers
- Ultra-thin film
- Residue detection

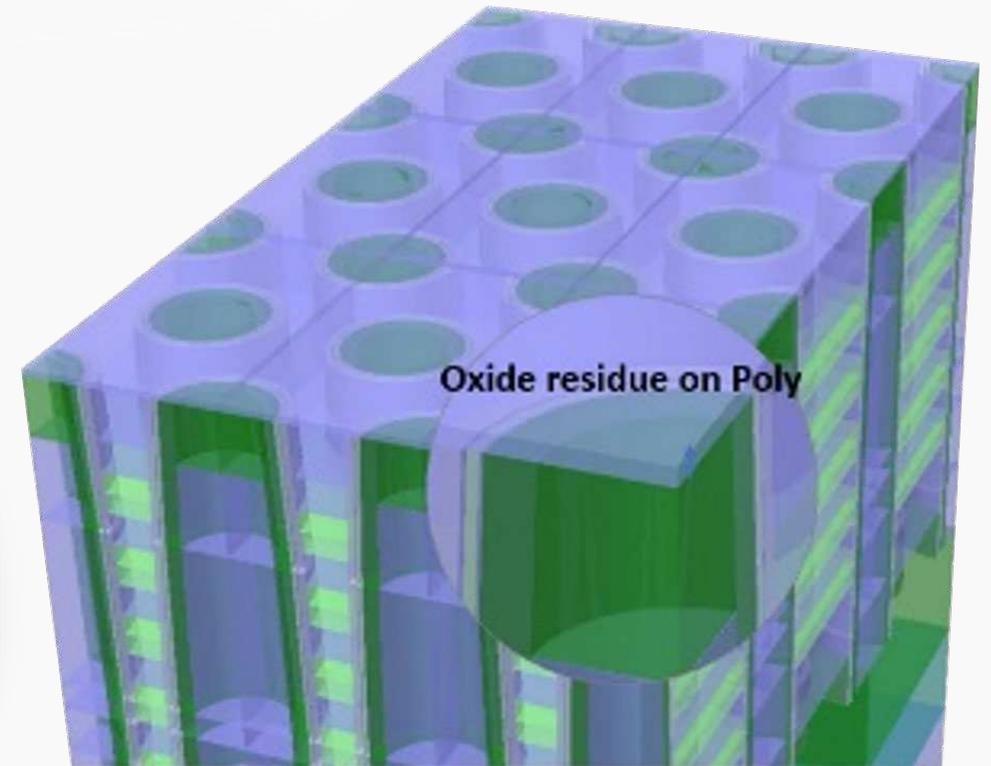
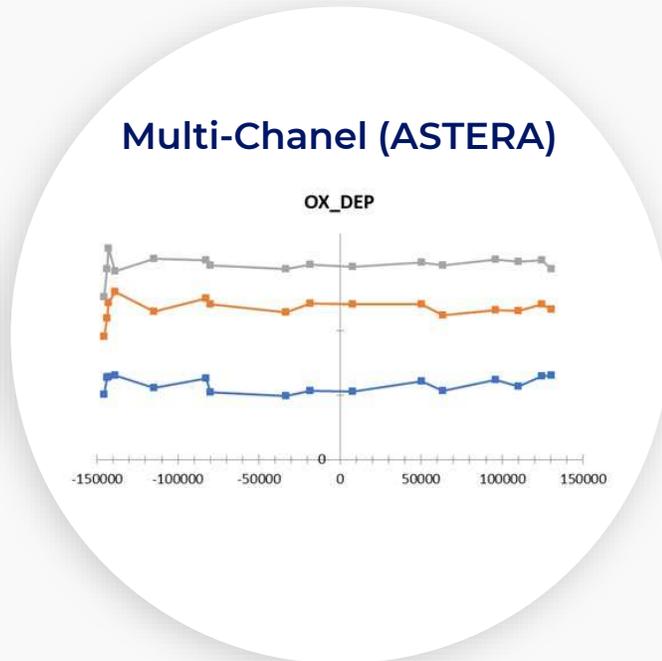
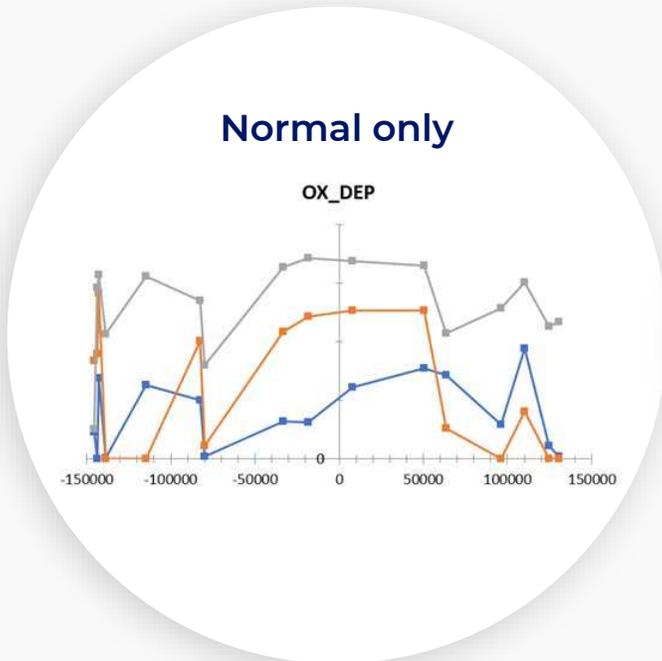


Multi-Channel Integrated Metrology

Case Study: Residue Detection in 3D NAND



- Demonstrated measurement sensitivity of below 20Å
- Oblique channel as enabler to solve thin film on structure
- Improved accuracy and stable WiW variation
- 50% precision improvement VS normal only



Spectral Interferometry (SI)

Unique Optical CD Technology: Hardware & Software



SI

Added on top of advanced Reflectometry (SR) & Ellipsometry (SE)

New Data

Extract complete wave-front of measured sample (inaccessible by other methods)

Unique HW

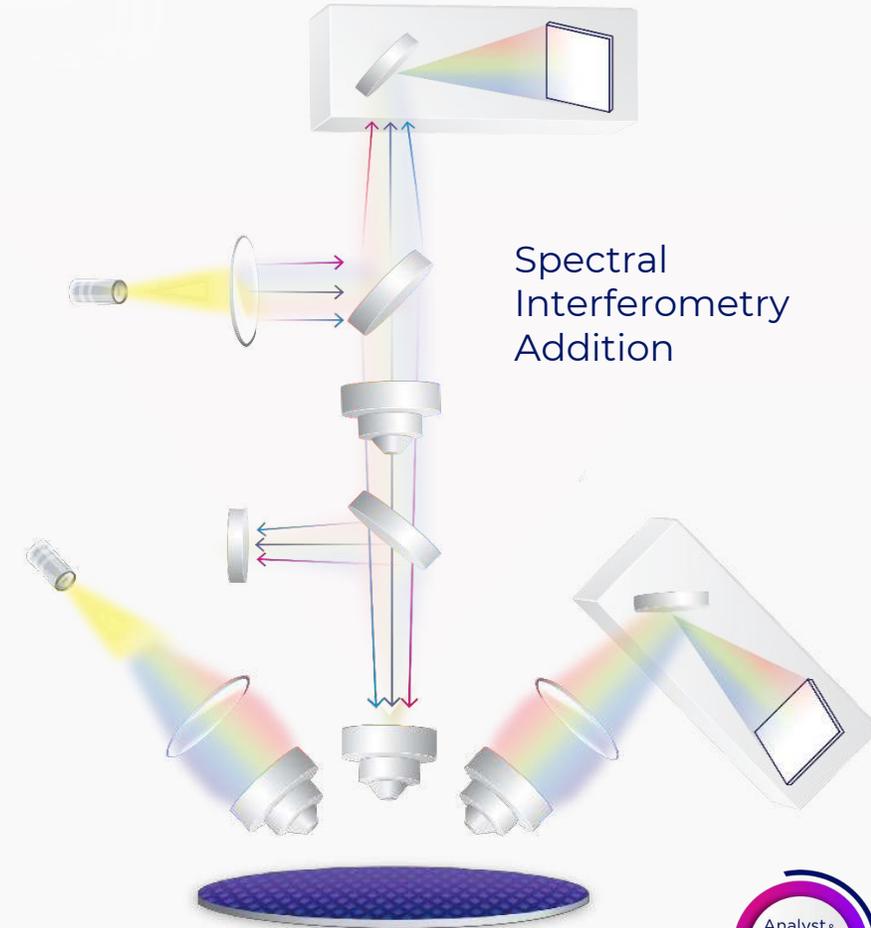
“Interferometry-like”

HW-SW Synergy

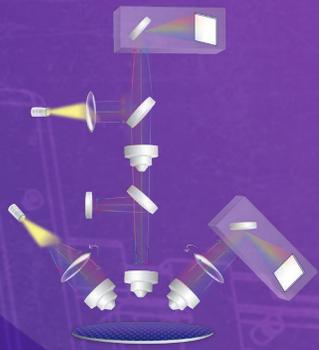
Proprietary algorithms using unique information (physical & mathematical modeling)

Synergy Enables

- Depth-profiling and underlayer filtering
- Enhanced performance on multiple use-cases



NOVA

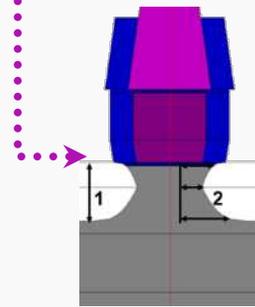
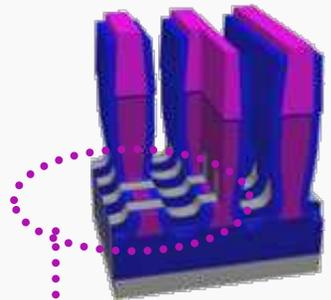


Spectral Interferometry

Example Use Cases

Unique profile information

Logic Source/
Drain etch

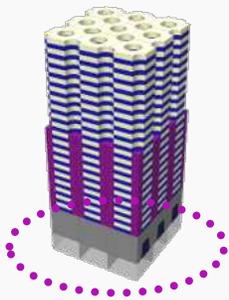


Underlayer filtering
depth-based separation

Top deck
applications

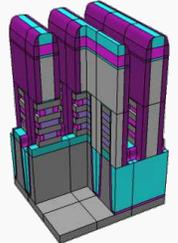


CMOS underlayer
architecture



Depth-based separation

Individual Nanosheet
properties (*)



(*) SPIE 2021: OCD enhanced: implementation and validation of spectral interferometry for nanosheet inner spacer indentation

XPS In-Line for Materials Metrology

The Market Standard for Ultra Thin Films



XPS

Inline non-destructive X-Ray for composition & thickness
(World unique)

Beyond optics

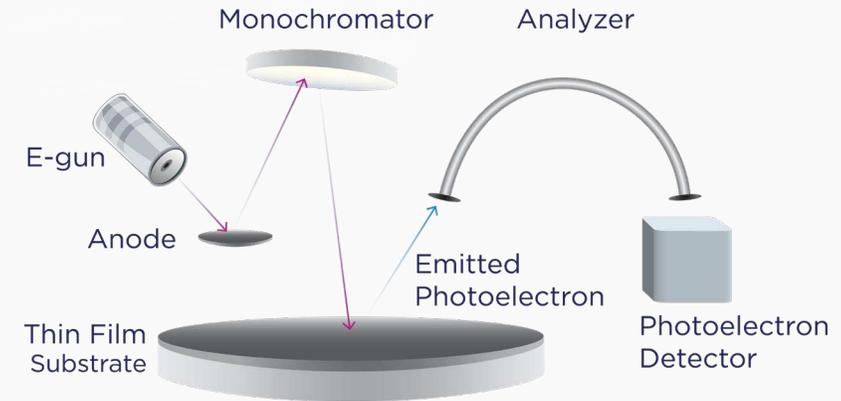
Precise control of ultra-thin films (e.g. HfO),
enabling accurate Vt tuning

XRF

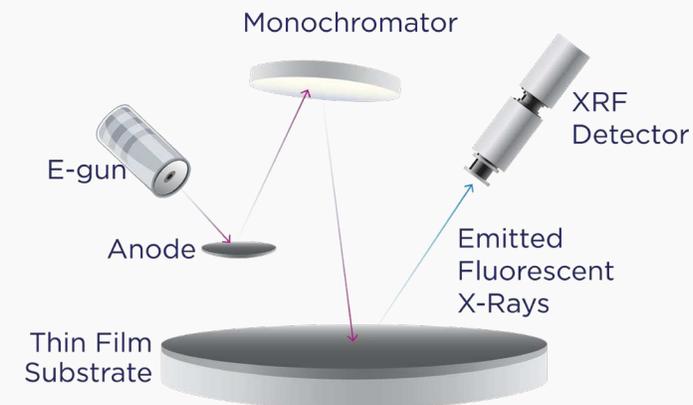
Simultaneous measurement for complex multi-stacks
(e.g. SiGeB)

In-die on-product measurement of advanced DRAM
and HAR 3DNAND (e.g. SiON)

Enabling process innovation – pattern selectivity and partial
coverage in **Selective Deposition**

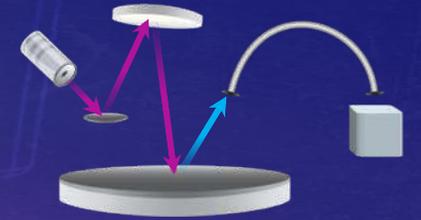


Non-Destructive



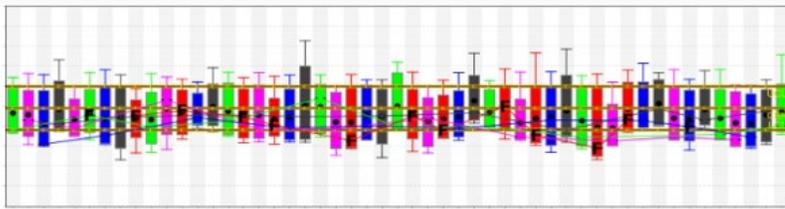
XPS for Materials Metrology

Example Use Cases

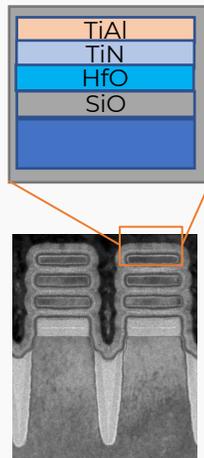
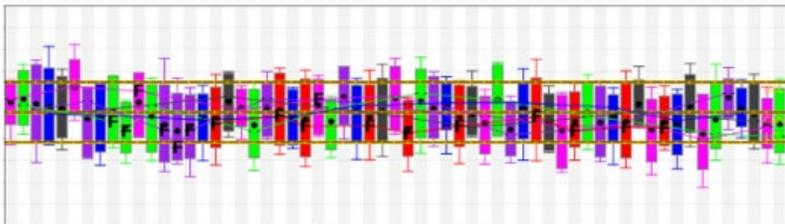


Nanosheet: Thickness and composition control

Ti:Al % Composition Control

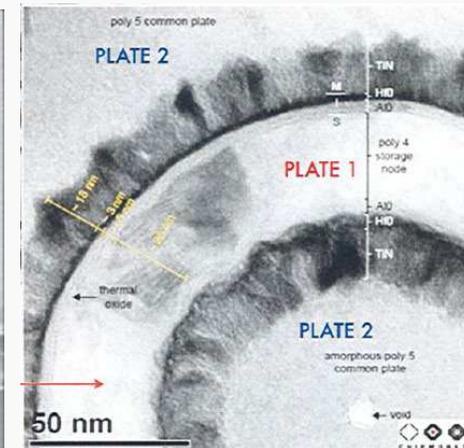
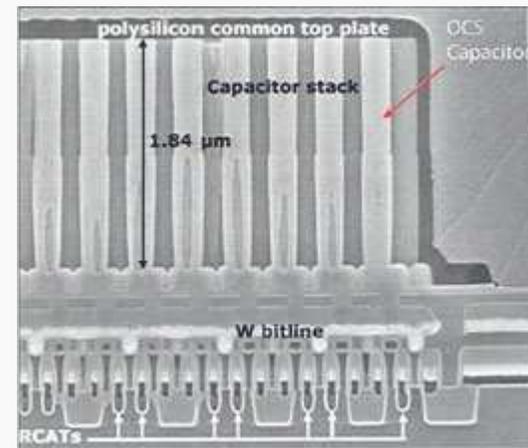


HfO Thickness Control



In line XPS and XRF deliver precise control of thickness and composition for complex gate stack film structures

DRAM: Complex High-K multi stack thickness control

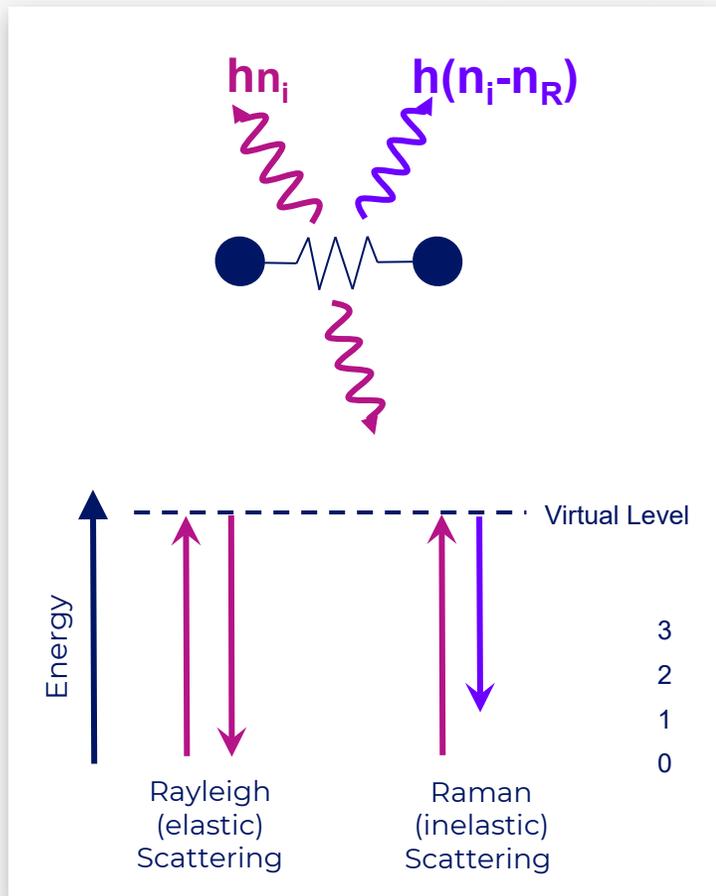


Only surface sensitive XPS can provide direct control of complex High-K dielectric stack in-die

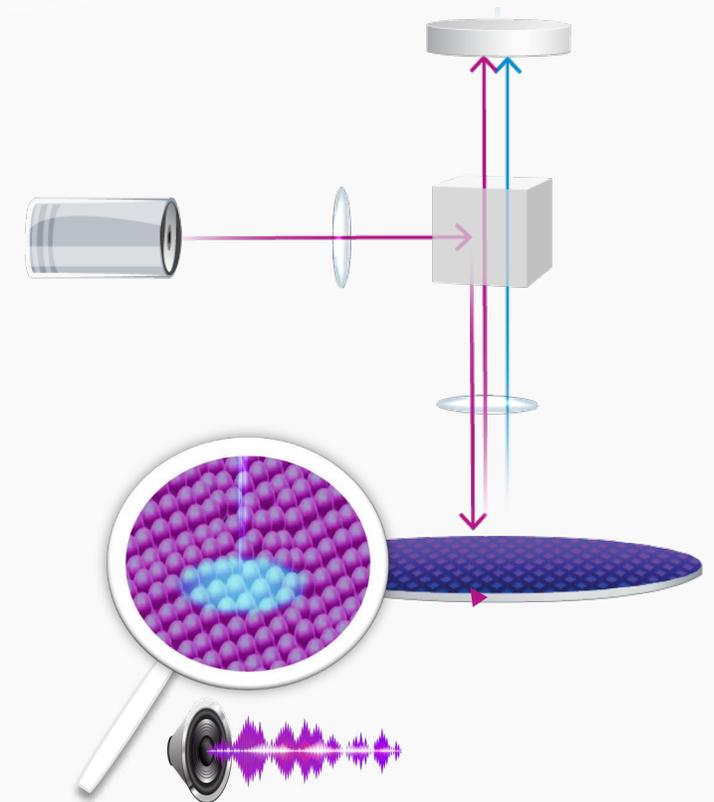
Raman Spectroscopy

For Materials Metrology

Unique
to Nova



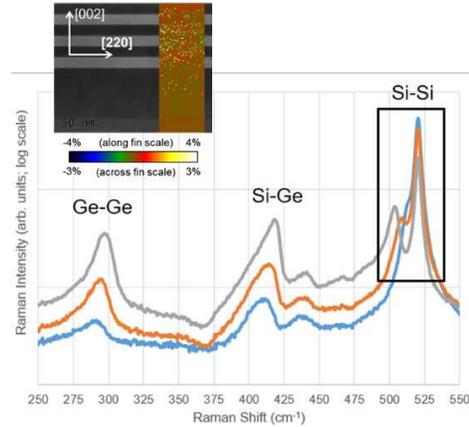
- Known powerful, optical technique for material characterization
- Small-spot on-structure metrology
- Sensitive to multiple material properties
- HVM-ready in-line Raman
- Algorithm and modeling: translating raw Raman spectra to SPC level data



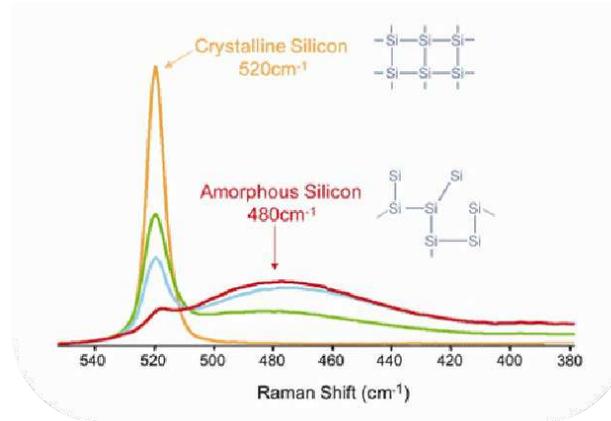
Raman Application Space

Validated by Leading Logic & Memory Customers

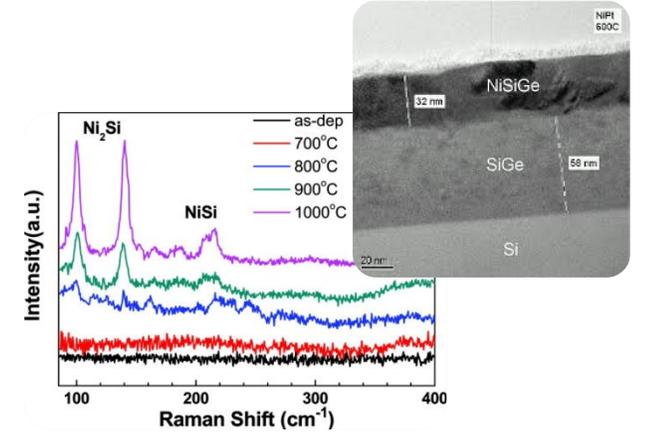
Strain in Channel and Source/ Drain*



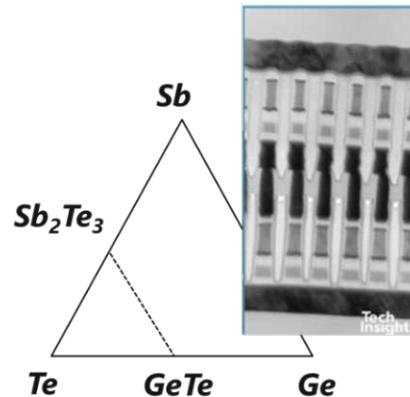
Crystallinity



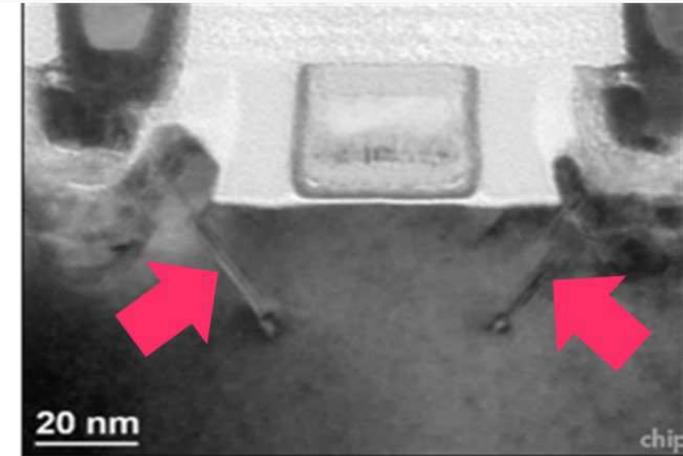
Phases and Grain-size



PCM Crystallinity



Defectivity



* SPIE 2021: In-line Raman spectroscopy for stacked nanosheet device manufacturing

From Lab to Fab

A Complex Journey



Automation

- Fully automated HW and measurement sequence
- Recipe-driven 300mm wafers

HVM Worthy

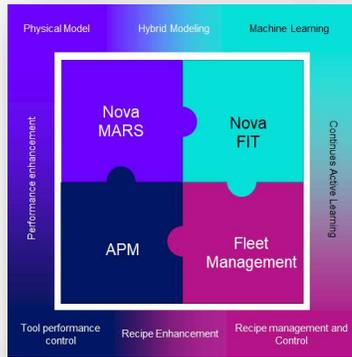
- Fab connectivity for statistical process control
- Non-destructive

Peak Performance

- High throughput, accuracy & repeatability
- Algorithm suite for material information analysis



Comprehensive Modeling



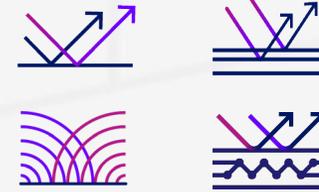
Benefits

- Accuracy & robustness → tighter process specs
- Reduce (destructive) reference → time to market
- Expand applications → more process control
- More parameters → deeper process insights

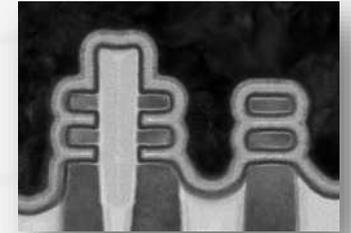
Unique Directions: Physical Modeling with Machine Learning



Physical Modeling



Nova Unique Reference

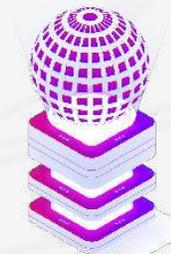


External Reference

SI, Raman, XPS, Multichannel IM

TEM, E-test

Nova Machine Learning



Source: Imec, 2021

Software & Hardware Synergy

The Best of Both Worlds

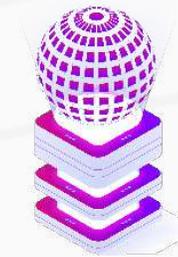
- Unique HW & dedicated algorithms
- Cross – platform synergy
- Continuously and actively optimize machine learning models



Nova PRISM



Nova MARS

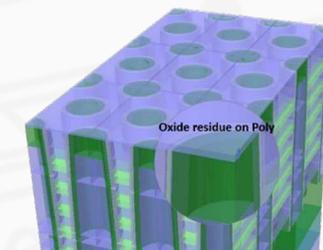


Nova FIT



IM for CMP

Under layer filtering via PRISM SI – Robust in-die solution for multi deck and CuA – Enhanced CMP control



Enhancing IM with XPS data via dedicated Machine Learning

Summary

Unique Technologies to Answer Key Challenges



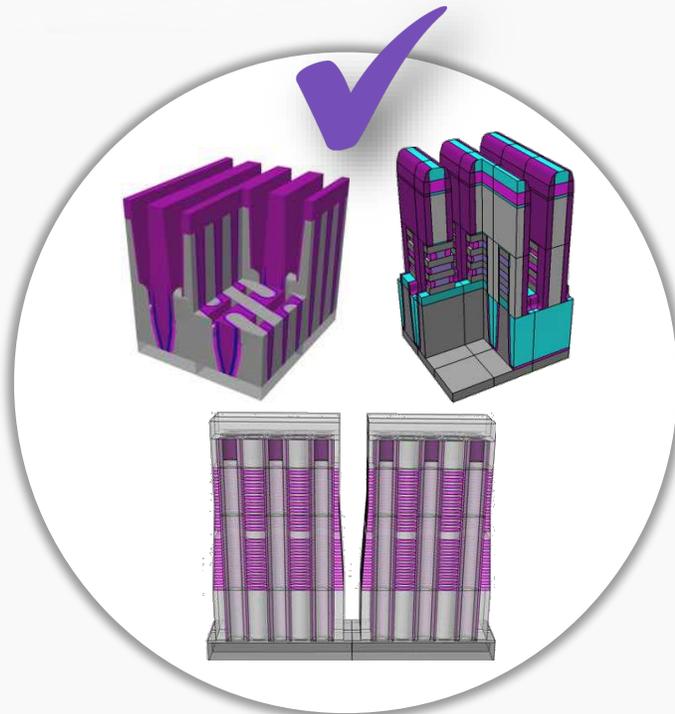
NOVA PRISM
Spectral Interferometry



NOVA ASTERA
Multi-Channel
Integrated
Metrology



Nova MARS
Nova FIT
Physical & Mathematical modeling



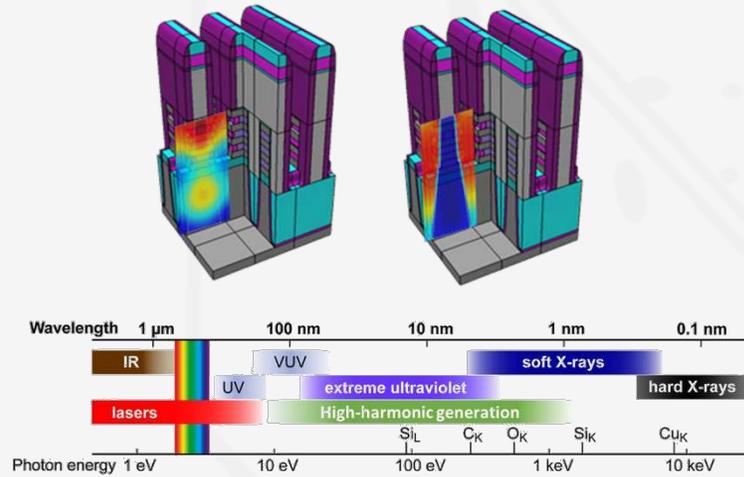
NOVA VERAFLEX
X-Ray:
XPS
and XRF



NOVA ELIPSON
Optical:
Raman
Spectroscopy

Future Directions

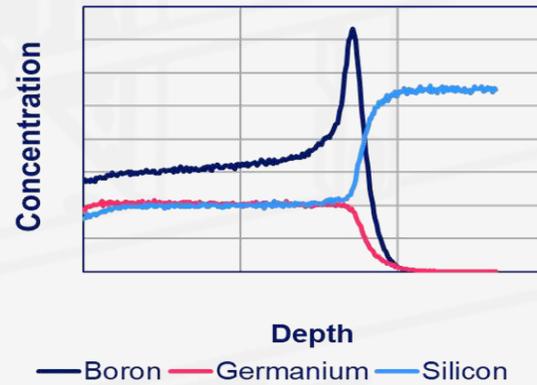
Dimensional



Different energy sources probe different dimensions of the structure

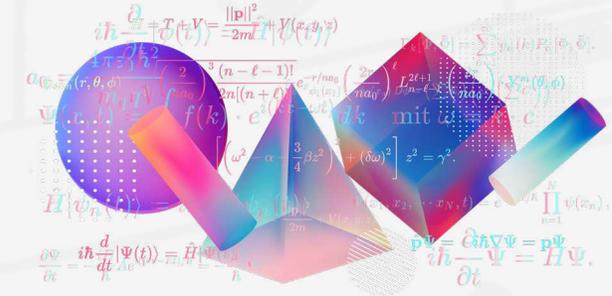
Materials

Boron Distribution Profile in SiGe



Depth-profile measurement

Software and Algorithms



Comprehensive Modeling – Physical and Mathematical



Closing Remarks

Eitan Oppenheim, President & CEO

Key Takeaways

Positioned for Continuous Growth



Growing demand for IC drives capacity & Increasing complexity
Increasing need for advanced metrology solutions



Unique and disruptive technology portfolio
Driving a stronger position and expanding TAM



Solid operational model
Supports clear strategy for growth

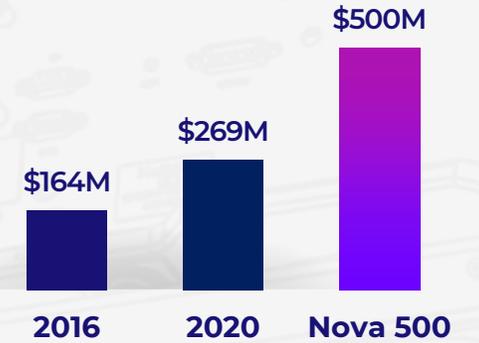


Proven performance towards Nova 500
Outperforming the Industry

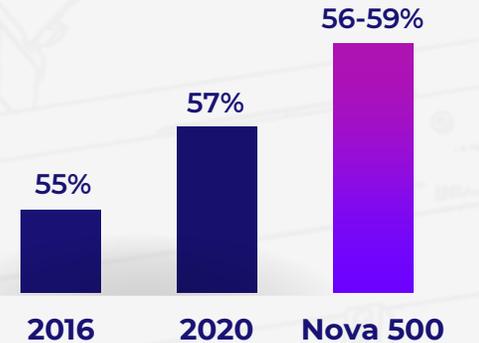


Cultural elevation with new CSR strategy
Combining businesses ethics with culture and social conciseness

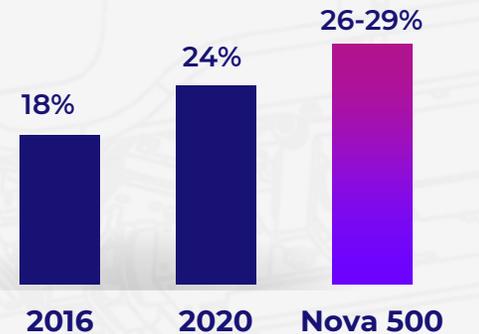
Revenue



Gross Margin



Operating Margin



Non-GAAP Financials



NOVA[®] PROCESS
INSIGHT

Thank You
